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(54) Photorealist composition

(57) Disclosed are photorealizable compositions having improved striping properties as well as methods for manufacturing printed wiring boards using such photorealizable compositions.

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Description

Background of the invention

5 [00001] This invention relates generally to the field of photoresists. In particular, this invention relates to the field of photoresists having improved stripping properties, especially suitable for use in printed wiring board manufacture.

10 [00002] Photoresists are photosensitive films used for transfer of images to a substrate. A coating layer of a photoresist is formed on a substrate and the photoresist layer is then exposed through a photomask to a source of activating radiation. The photomask has areas that are opaque to activating radiation and other areas that are transparent to activating radiation. Exposure to activating radiation provides a photoinduced chemical transformation of the photoresist coating to thereby transfer the pattern of the photomask to the photoresist-coated substrate. Following exposure, the photoresist is developed to provide a relief image that permits selective processing of a substrate.

15 [00003] A photoresist can be either positive-acting or negative-acting. For most negative-acting photoresists, those coating layer portions that are exposed to activating radiation polymerize or cross-link in a reaction between a photoactive compound and polymerizable agents of the photoresist composition. Consequently, the exposed coating portions are rendered less soluble in a developer solution than unexposed portions. For positive-acting photoresists, exposed portions are rendered more soluble in a developer solution while areas not exposed remain comparatively less developer soluble.

20 [00004] In general, photoresist compositions include at least a resin binder component, a monomer and a photoactive agent. A wide variety of polymeric or resin binders may be used in photoresists. Such polymeric binders may include, as polymerized components, one or more acid functional monomers such as acrylic acid or methacrylic acid. For example, U.S. Patent No. 5,952,153 (Lundy et al.) discloses photoimageable compositions containing polymeric binders having sufficient acid functionality to render the photoimageable composition developable in alkaline aqueous solution. U.S. Patent No. 4,537,865 (Ido) discloses polycarboxylic acids used to form polymerizable ester derivatives with ethylenically unsaturated compounds. Such polymerizable ester derivatives are used to form the polymeric binders for photoimageable compositions.

25 [00005] Monomers typically useful in photoresist compositions are any which are cross-linkable. Such monomers cross-link to form a polymerized network having a very large, i.e., infinite, molecular weight. The polymeric binders do not participate in such cross-linking. Rather, the monomers form a polymerized network around the polymeric binders. Typically, polymeric binders contain pendant groups, such as carboxylic acids that react with the developer to increase the water solubility of the binder. Thus, in the unexposed portion, the acid functional polymer is salted in the alkaline solution, while in the exposed area (protected by the cross-linked monomers), the polymer is not affected. During stripping, the polymerized network (of cross-linking monomers) is attacked or degraded by the stripper allowing it to be removed, whereas the polymeric binder remains relatively unaffected by such strippers.

30 [00006] Photoresists may be either liquid or dry film. Liquid photoresists are dispensed on a substrate and then cured. Dry film photoresists are typically laminated to a substrate. Such dry film photoresists are particularly suitable for use in printed wiring board manufacture. One problem with conventional dry film photoresist compositions is that they are difficult to strip from electrolytically plated circuit boards using conventional alkaline aqueous stripping solutions; e.g., 3% sodium hydroxide solution. This problem arises from the demand of circuit board manufacturers to reduce the size of printed circuit boards, while increasing their functional capabilities. Consequently, the circuit lines and spaces on the circuit boards have continued to shrink, as more circuitry needs to be accommodated in smaller spaces. At the same time, metal plating heights have also increased above the thickness of the photoresist. This causes the metal to hang over the photoresist, resulting in a very narrow space containing the photoresist being virtually encapsulated by the overplated metal. The photoresist then becomes trapped by the plated overhang, making it difficult to attack and strip by conventional methods. If the photoresist is not completely stripped or removed, ragged copper circuit lines will result after etching which are unsuitable as they can cause short circuiting of the board.

35 [00007] Some circuit board manufacturers have tried thicker photoresists to accommodate the increasing plating heights, however, this approach is more expensive and limits resolution of the circuit lines. Typically, organic-based (amine- or organic solvent-containing) alkaline stripping solutions are used which produce a smaller stripped particle to facilitate stripping. While such organic-based strippers remove the resist better, they are expensive relative to inorganic-based strippers (e.g., sodium or potassium hydroxide) and have more waste treatment and environmental concerns associated with them. Solvent-strippable photoresists are much less desirable due to workplace regulations limiting or reducing solvent emissions.

40 [00008] Certain polymer binders have been described optionally containing one or more multifunctional monomers. For example, U.S. Patent No. 5,839,239 (Lundy et al.) discloses polymer binders containing acid functional monomers optionally copolymerized with another monomer, including certain multifunctional monomers. The multifunctional monomers disclosed are tri- or tetra-functional (meth)acrylates esters or relatively low molecular weight, i.e., typically ≤ 450 , difunctional (meth)acrylates esters. Polymer binders containing such tri- and tetra-functional monomers or such rela-

tively low molecular weight difunctional (meth)acrylate esters suffer from gel formation, which makes such polymers unsuitable for use in photoresist compositions.

[0009] It is thus desirable to provide photoresist compositions that are easily removed using alkaline aqueous inorganic-based etching solutions, and that do not form gels.

Summary of the Invention

[0010] It has been surprisingly found that branched binder polymers including branch-point monomers as polymerized units provide photoimageable compositions having improved stripability or removability. It has also been surprisingly found that such branch-point monomers as polymerized units do not adversely affect other properties of the photoimageable composition such as chemical resistance. Further, it has been found that the present branched binder polymers are not subject to gel formation.

[0011] In one aspect, the present invention provides a photoresist composition including a branched polymeric binder, a monomer and a photoactive component, wherein the branched polymeric binder includes as polymerized units one or more difunctional branch-point monomers having two polymerizable end groups and a backbone including one or more base cleavable functionalities, provided that if the difunctional branch-point monomer is free of urethane linkages and both polymerizable end groups are (meth)acrylate esters the difunctional branch-point monomer has a molecular weight of ≥ 450 .

[0012] In another aspect, the present invention provides a method of manufacturing a printed wiring board including the steps of: a) disposing on a printed wiring board substrate a photoresist composition including a branched polymeric binder, a monomer and a photoactive component, wherein the branched polymeric binder includes as polymerized units one or more difunctional branch-point monomers having two polymerizable end groups and a backbone including one or more base cleavable functionalities, provided that if the difunctional branch-point monomer is free of urethane linkages and both polymerizable end groups are (meth)acrylate esters the difunctional branch-point monomer has a molecular weight of ≥ 450 ; b) imaging the photoresist; and c) developing the photoresist.

[0013] In a further aspect, the present invention provides a method for forming a relief image including the steps of: a) disposing on a printed wiring board substrate a photoresist composition including a branched binder, a monomer and a photoactive component, wherein the branched polymeric binder includes as polymerized units one or more difunctional branch-point monomers having two polymerizable end groups and a backbone including one or more base cleavable functionalities, provided that if the difunctional branch-point monomer is free of urethane linkages and both polymerizable end groups are (meth)acrylate esters the difunctional branch-point monomer has a molecular weight of ≥ 450 ; b) imaging the photoresist; and c) developing the photoresist.

[0014] In a still further aspect, the present invention further provides a compound having the formula A-Z-B wherein A and B each include one or more polymerizable groups and Z includes one or more base cleavable groups, wherein the compound has a molecular weight of ≥ 450 .

Detailed Description of the Invention

[0015] As used throughout this specification, the following abbreviations shall have the following meanings, unless the context clearly indicates otherwise: °C = degrees Centigrade; g = grams; mg = milligrams; mJ = millijoules; μm = micron = micrometer; Tg = glass transition temperature; °F = degrees Fahrenheit; wt% = percent by weight; and ml = 0.001 inch.

[0016] The terms "resin" and "polymer" are used interchangeably throughout this specification. The term "alkyl" refers to linear, branched and cyclic alkyl. The terms "halogen" and "halo" include fluoro, chloro, bromine, and iodine. Thus the term "halogenated" refers to fluorinated, chlorinated, brominated, and iodinated. "Polymers" refer to both homopolymers and copolymers and include dimers, trimers, oligomers and the like. The term "(meth)acrylate" refers to both acrylate and methacrylate. Likewise, the term "(meth)acrylic" refers to both acrylic and methacrylic. "Monomer" refers to any ethylenically or acetylenically unsaturated compound capable of being polymerized. As used throughout this specification, the term "branch-point monomer" refers to any compound containing two or more polymerizable groups and having one or more base cleavable functionalities in its backbone disposed between the two or more polymerizable groups. "Difunctional branch-point monomer" refers to a branch-point monomer having only two polymerizable end groups, i.e. two end groups that are polymerized into the binder polymer backbone. A "branched" polymer refers to a polymer having an interconnected network, such as interconnected to form a three-dimensional network, but having a finite molecular weight. The terms "cross-linker" and "cross-linking agent" are used interchangeably throughout this specification. The terms "printed wiring board" and "printed circuit board" are used interchangeably throughout this specification. A "pendant group" refers to any group suspended from a polymer, i.e. only one end of the group is attached to the polymer. Such "pendant group" is not part of the backbone of the polymer.

[0017] All amounts are percent by weight and all ratios are by weight, unless otherwise noted. All numerical ranges

[0019] A wide variety of polymeric binders are suitable for use in the present invention. Suitable polymeric binders are those containing as polymerized units one or more ethylenically or acetylenically unsaturated monomers and one or more difunctional branch-point monomers having two polymerizable end groups and a backbone including one or more base cleavable functionalities, provided that if the difunctional branch-point monomer is free of urethane linkages and both polymerizable end groups are (meth)acrylate esters the difunctional branch-point monomer has a molecular weight of ≥ 450 . Suitable ethylenically or acetylenically unsaturated monomers include, but are not limited to: (meth)acrylic acid, (meth)acrylamides, alkyl (meth)acrylates, alkenyl (meth)acrylates, aromatic (meth)acrylates, vinyl aromatic monomers, nitrogen-containing compounds and their thio-analogs, substituted ethylene monomers, cyclic olefins, substituted cyclic olefins, and the like. Preferred monomers include (meth)acrylic acid, alkyl (meth)acrylates and vinyl aromatic monomers.

[0021] "Low cur" alkyl (meth)acrylates are typically those where the alkyl group contains from 1 to 6 carbon atoms. Suitable low cur alkyl (meth)acrylates include, but are not limited to: methyl methacrylate, methyl acrylate, ethyl acrylate, propyl methacrylate, butyl methacrylate, butyl acrylate, isobutyl methacrylate, hexyl methacrylate, cyclohexyl methacrylate, cyclohexyl acrylate and mixtures thereof.

“High cut” alkyl (meth)acrylates are typically those where the alkyl group contains from 16 to 24 carbon atoms. Suitable high cut alkyl (meth)acrylates include, but are not limited to: hexadecyl methacrylate, heptadecyl methacrylate, octadecyl methacrylate, nonadecyl methacrylate, cosyl methacrylate, cicosyl methacrylate and mixtures thereof. Particularly useful mixtures of high cut alkyl (meth)acrylates include, but are not limited to: cosyl-cicosyl methacrylate, Paralene[®] 1000, which is a mixture of hexadecyl, octadecyl, cosyl and cicosyl methacrylate, and cetyl-stearyl methacrylate, which is a mixture of hexadecyl and octadecyl methacrylate.

[0025] The alkyl (meth)acrylate monomers useful in the present invention may be a single monomer or a mixture having different numbers of carbon atoms in the alkyl portion. Also, the (meth)acrylamide and allyl (meth)acrylate monomers useful in the present invention may optionally be substituted. Suitable optionally substituted (meth)acrylamide and allyl (meth)acrylate monomers include, but are not limited to: hydroxy(C_2-C_6)allyl (meth)acrylates, dialkylamino(C_2-C_6)allyl (meth)acrylates, dialkylamino(C_2-C_6)allyl (meth)acrylamides.

[0026] Particularly useful substituted alkyl (meth)acrylate monomers are those with one or more hydroxyl groups in the alkyl radical, especially those where the hydroxyl group is found at the β-position (2-position) in the alkyl radical.

[0027] Other substituted (meth)acrylate and (meth)acrylamide monomers useful in the present invention are those with a dialkylamino group or dialkylaminooxy group in the alkyl radical. Examples of such substituted (meth)acrylates and (meth)acrylamides include, but are not limited to: dimethylaminoethyl methacrylate, dimethylaminoethyl acrylate, N,N-dimethylaminoethyl methacrylamide, N,N-dimethyl- α -aminopropyl methacrylate, N,N-diethylaminoethyl methacrylamide, N,N-diethylaminoethyl methacrylamide, N,N-diethylaminoethyl methacrylamide, N,N-diethylaminoethyl methacrylamide, N-(1-methylethyl)-3-oxobutyl methacrylamide, N-(1,3-diphenyl-1-ethyl-3-oxobutyl) acrylamide, N-(1-methyl-1-phenyl-3-oxobutyl) methacrylamide, and 2-hydroxyethyl acrylamide. N-methylacrylamide of aminoethyl ethylene urea, N-methacryloxy ethyl morpholine, N-maleinimide of dimethylaminopyrrolamine and mixtures thereof.

[0026] Other substituted (meth)acrylate monomers useful in the present invention are silicon-containing monomers such as γ -propyl tri(C₁-C₆)alkoxysilyl (meth)acrylate, γ -propyl tri(C₁-C₆)alkylsilyl (meth)acrylate, γ -propyl di(C₁-C₆)alkoxysilyl (meth)acrylate, γ -propyl di(C₁-C₆)alkylsilyl (meth)acrylate, vinyl tri(C₁-C₆)alkoxysilyl (meth)acrylate, vinyl di(C₁-C₆)alkoxysilyl (meth)acrylate, vinyl tri(C₁-C₆)alkylsilyl (meth)acrylate, vinyl di(C₁-C₆)alkylsilyl (meth)acrylate, vinyl tri(C₁-C₆)alkoxysequibutane(meth)acrylate and mixtures thereof.

[0029] The vinyl aromatic monomers useful as unsaturated monomers in the present invention include, but are not limited to: styrene, hydroxystyrene, α -methylstyrene, vinyltoluene, p -methylstyrene, ethylvinylbenzene, vinylnaphthalene, vinylxylenes, and mixtures thereof. The vinylaromatic monomers also include their corresponding substituted counterparts, such as halogenated derivatives, i.e., containing one or more halogen groups, such as fluorine, chlorine or bromine; and nitro, cyano, $(C_1-C_{10}alkoxy, halo(C_1-C_{10}alkyl, carb(C_1-C_{10}alkoxy, carboxy, amino, (C_1-C_{10}alkylamino derivatives and the like.$

[0030] The nitrogen-containing compounds and their thio-analogs useful as unsaturated monomers in the present invention include, but are not limited to: vinylpyridines such as 2-vinylpyridine or 4-vinylpyridine; (C₁-C₈) alkyl substituted N-vinyl pyridines such as 2-methyl-5-vinyl-pyridine, 2-ethyl-5-vinylpyridine, 3-methyl-5-vinylpyridine, 2,3-dimethyl-5-vinyl-pyridine, and 2-methyl-3-ethyl-5-vinylpyridine; methyl-substituted quinolines and isquinolines; N-vinylcarbazole; N-vinylbutylacrylamide; N-vinylpyrrolidone; vinyl imidazole; N-vinyl carbazole; N-vinyl-succinimide; (meth)acrylonitrile; *o*-, *m*-, or *p*-aminostyrene; maleimide; N-vinyl-oxazolidone; N,N-dimethyl aminoethyl-vinyl-ether, ethyl-2-cyanoacrylate, vinyl acetone; N-vinylphthalimide; N-vinyl-pyrrolidones such as N-vinyl-thio-pyrrolidone, 3 methyl-1-vinyl-pyrrolidone, 4-methyl-1-vinyl-pyrrolidone, 5-methyl-1-vinyl-pyrrolidone, 3-butyl-1-vinyl-pyrrolidone, 3,3-dimethyl-1-vinyl-pyrrolidone, 4,5-dimethyl-1-vinyl-pyrrolidone, 5,5-dimethyl-1-vinyl-pyrrolidone, 3,3,5-trimethyl-1-vinyl-pyrrolidone, 4-ethyl-1-vinyl-pyrrolidone, 5-methyl-5-ethyl-1-vinyl-pyrrolidone and 3,4,5-trimethyl-1-vinyl-pyrrolidone; vinyl pyrroles; vinyl anilines; and vinyl piperidines.

[0031] The substituted ethylene monomers useful as unsaturated monomers is in the present invention include, but are not limited to: vinyl acetate, vinyl formamide, vinyl chloride, vinyl fluoride, vinyl bromide, vinylidene chloride, vinylidene fluoride, vinylidene bromide, tetrafluoroethylene, trifluoroethylene, trifluoromethyl vinyl acetate, vinyl ethers and itaconic anhydride.

[0032] Suitable cyclic olefin monomers useful in the present invention are (C_5-C_{10})cyclic olefins, such as cyclopentene, cyclopentadiene, dicyclopentene, cyclohexene, cyclohexadiene, cycloheptene, cycloheptadiene, cyclooctene, cyclooctadiene, norbornene, maleic anhydride and the like. Such cyclic olefins also include spirocyclic olefin monomers such as spirocyclic norbornenyl monomers, spirocyclic cyclohexene monomers, spirocyclic cyclopentene monomers and mixtures thereof. Suitable substituted cyclic olefin monomers include, but are not limited to, cyclic olefins having one or more substituent groups selected from hydroxy, alkoxy, halo, (C_1-C_2)alkyl, (C_1-C_2)haloalkyl, (C_1-C_2)hydroxy-alkyl, (C_1-C_2)halohydroxyalkyl such as (CH_2)_n $C(CF_3)_2OH$ where n = 0 to 4, (C_1-C_2)alkoxy, thio, amino, (C_1-C_6)alkylamino, (C_1-C_6)dialkylamino, (C_1-C_2)allylthio, carbo(C_1-C_2)alkoxy, carbo(C_1-C_2)haloalkoxy, (C_1-C_2)acyl, (C_1-C_6)alkylcarbamoyl/ (C_1-C_6) alkyl, and the like. Particularly suitable substituted substituted cyclic olefins include maleic anhydride and cyclic olefins containing one or more of hydroxy, alkoxy, arylalkoxy, (C_1-C_2)alkyl, (C_1-C_2)haloalkyl, (C_1-C_2)hydroxyalkyl, carbo(C_1-C_2)alkoxy, and carbo(C_1-C_2)haloalkoxy. It will be appreciated by those skilled in the art that the alkyl and alkoxy substituents may be optionally substituted, such as with halogen, hydroxy, cyano, (C_1-C_6)alkoxy, mercapto, (C_1-C_6)alkylthio, amino, acid labile leaving group and the like. Suitable carbo(C_1-C_2)alkoxy substituents include, but are not limited to, those of the formula C(O)O-LG, wherein LG is a leaving group including, but are not limited to, alkyl groups having 4 or more carbon atoms with at least one quaternary carbon atom bonded directly to a carbonylate oxygen such as tert-butyl esters, 2,3-dimethylbutyl esters, 2-methyphenyl esters, 2,3,4-trimethylphenyl esters, alkylcylic esters, acetals or ketals from vinyl ethers or enols such as O-(CH(CH₃)OC(CH₃)₂) or O-(CH₂OC(CH₃)₂), tetrahydropyran. Suitable alkylcylic esters as leaving groups include adamantyl, methyladamantyl, ethyladamantyl, methylnorbornyl, ethynorbornyl, ethyltrimethylnorbornyl, ethyl fenchol and the like.

where A and B each include one or more polymerizable groups, and Z includes one or more base cleavable groups. Suitable base cleavable groups for A and B include, but are not limited to, isocyanate (NCO^*), $\text{RR}^1\text{C}=\text{CR}^2$, $\text{R}^3\text{C}=\text{C}$, $\text{RR}^1\text{C}=\text{CR}^2(\text{O})-\text{O}$, $\text{RR}^1\text{C}=\text{CH}^2-\text{O}$, and $-\text{C}(\text{O})-\text{O}-\text{R}^3$, wherein R^1 , R^2 and R^3 are independently selected from H , $(\text{C}_1-\text{C}_6)\text{alkyl}$, R^4 , R^5 and R^6 are independently selected from H , $(\text{C}_1-\text{C}_6)\text{alkyl}$, in addition to one or more base cleavable groups, the group Z may optionally include one or more spacer groups. Z may suitably have the general formula S_1BCG_1 , wherein S_1 is a spacer group, BCG is a base cleavable group, $x = 0-20$ and $y = 1-30$. It is preferred that $y = 2-20$. Suitable spacer groups include, but are not limited to, allyleneoxy, aryleneoxy, $(\text{C}_1-\text{C}_{20})\text{alkylene}$, substituted $(\text{C}_1-\text{C}_{20})\text{alkylene}$, $(\text{C}_8-\text{C}_{20})\text{aralkylene}$, and the like. Suitable allyleneoxy groups have the general formula $(-\text{CH}(\text{R}^6)-\text{CH}_2-\text{O})_m$, $(-\text{OCH}(\text{R}^6)-\text{CH}_2)_m$ or $(-\text{O}-\text{CH}_2-\text{CH}_2-\text{CH}_2)_p$, where R^6 is H or CH_3 , and n , m and p are each 1-1000. Exemplary allyleneoxy groups include ethyleneoxy, propyleneoxy and ethyleneoxy/propyleneoxy mixtures. Aryleneoxy or arylene ether spacers include phenyleneoxy (phyleneo aryl) spacers having the general formula $(-\text{C}_6\text{H}_4-\text{O})_q$, where $q = 1-1000$, biphenylene ethers, phenanthryl ethers, naphthyl ethers, and mixtures thereof. It will be appreciated that the spacer groups may independently be comprised of one or more of the above examples. When two or more spacer groups are used, they may be the same or different.

[0035] "Substituted alkyl" refers to any alkyl group having one or more of its hydrogens replaced by another substituent group selected from halo, cyano, hydroxyl, (C₁-C₆)alkoxy, armino, (C₁-C₆)allylamino, phenyl, carb(C₁-C₆)alkoxy, and the like. Likewise, "substituted aralkyl" refers to any aralkyl group having one or more of its hydrogens replaced by another substituent group selected from halo, cyano, hydroxyl, (C₁-C₆)alkoxy, armino, (C₁-C₆)allylamino, phenyl, carb(C₁-C₆)alkoxy, and the like.

[0036] Such spacer groups may be selected to provide additional properties. For example, alkylenoxy spacers, such as ethylenoxy and/or propylenoxy moieties, may help to emulsify the polymeric binders for use in water borne photoresists. Spacers having extended chain length may also provide improved flexibility and be particularly useful in conformal photoresist formulations. The choice of such spacer groups will depend upon the particular use of the polymer and the other components in the formulation, and is within the ability of one skilled in the art.

[0037] Any base cleavable group is suitable for use in Z, but is preferably selected from anhydrides ($-C(O)-O-C(O)-$), esters ($-C(O)-O-$), carbonates, silyl ether esters ($-SO_2-O-$) and the like, and more preferably esters. It is more preferred that the difunctional branch-point monomers contain 2 or more base cleavable groups and still more preferably 3 or more base cleavable groups. Particularly suitable difunctional branch-point monomers contain 4 base cleavable groups, and more particularly 4 or more ester linkages. It is further preferred that the difunctional branch point monomer contain as polymerizable and groups moieties that also contain one or more base cleavable functionalities, such as (meth)acrylates esters. When the difunctional branch-point monomers contain 2 or more base cleavable groups, such groups may be directly bonded to each other or may be separated by one or more spacer groups. An exemplary structure for such branch-point monomers having multiple base cleavable groups is $A-(S1)_x1-BCG1-(S2)_x2-BCG2-(S3)_x3-B$, wherein S1, S2 and S3 refer to spacer groups 1-3, respectively, BCG1 and BCG2 refer to base cleavable groups 1 and 2, respectively, $x1 + x2 + x3 = 0-20$, and A, B, S, BCG and B are as defined above. Other suitable structures having more or fewer spacers and/or base cleavable groups or different configurations of such groups are well within the ability of those skilled in the art.

[illegible]

hdi-pg425-hdi-pq0230-hdi-pg425-hdi-eghem, eghem-hdi-pg1000-hdi-pq0230-hdi-pg1000-hdi-eghem, eghem-hdi-pq0230-hdi-pg425-hdi-pq0230-hdi-eghem, and eghem-hdi-pg1000-hdi-pq0201-hdi-pg1000-hdi-eghem. In the above described difunctional branch-point monomers, each "dash" represents a urethane group (formed when an isocyanate group reacts with a hydroxyl group) between the adjacent moieties. Such urethane linkages are not required in the present branch-point monomers. The abbreviations for the moieties are: hdi = 1,6-hexamethylene diisocyanate; pq0200 = TONEM[™] Polyol 0200 Diol (containing carboxylic ester groups); pq0201 = TONEM[™] Polyol 0201 Diol (contains carboxylic ester groups); pq0230 = TONEM[™] Polyol 0230 Diol (contains carboxylic ester groups); pg425 = polypropylene glycol having a molecular weight of approximately 425; pg1000 = polypropylene glycol having a molecular weight of approximately 1000; dmga = dimethylolpropionic acid; pdmtl = 3-isopropenyl-alpha, alpha-dimethylbenzyl isocyanate; Ziemna = 2-hydroxyethyl methacrylate (contains ester group and a polymerizable end group); eghem = ethoxylated hydroxyethyl methacrylate (contains ester group and a polymerizable end group); and etbc14 = ethoxylated caprolactone-derived methacrylate (contains ester groups and a polymerizable end group). Such branch-point monomers are generally commercially available or may be readily prepared by known methods. TONEM[™] is a trademark for polycaprolactone diols, available from the Dow Chemical Company (Midland, Michigan). Other suitable polycaprolactone diols are available from Solway under the CAPA brand name. Typically, the molecular weight of the branch-point monomers is ≥ 450 , and preferably from 450 to 6000.

[0039] The branched polymeric binders of the present invention include as polymerized units one or more difunctional branch-point monomers having two polymerizable end groups and a backbone including one or more base cleavable functionalities, provided that if the difunctional branch-point monomer is free of urethane linkages and both polymerizable end groups are (meth)acrylate esters the difunctional branch-point monomer has a molecular weight of ≥ 450 . When polymeric binders are prepared from tri-, tetra- or higher-functional branch-point monomers, i.e., those containing 3 or more polymerizable end groups, such polymeric binders are much more likely to suffer from gel formation, which makes such binders unsuitable for use in photoresist compositions. Further, when polymeric binders are prepared from relatively low molecular weight, i.e., ≥ 450 , difunctional branch-point monomers containing no urethane linkages and containing (meth)acrylate esters as both polymerizable end groups, such polymeric binders also suffer from gel formation. Such gel formation is not a problem when the difunctional branch-point monomers are higher molecular weight, i.e., ≥ 450 , monomers containing (meth)acrylate esters as both polymerizable end groups, or when such monomers contain one or more urethane linkages.

[0040] The present invention further provides a compound having the formula A-Z-B, wherein A and B each include one or more polymerizable groups and Z includes one or more base cleavable groups, wherein the compound has a molecular weight of ≥ 450 .

[0041] It will be appreciated by those skilled in the art that more than one difunctional branch-point monomer may be used to prepare the branched binder polymers of the present invention. Thus, mixtures of difunctional branch-point monomers may advantageously be used in the present invention. Typically, the total amount of such difunctional branch-point monomers in the branched binder polymers is from 0.1 to 100 wt% based upon the total weight of the monomers used to prepare the binder polymer, preferably from 0.1 to 25 wt%, and more preferably from 0.1 to 10 wt%.

[0042] The branched binder polymers of the present invention may be prepared by a variety of methods known in the art, such as free radical polymerization.

[0043] It will be appreciated that mixtures of binder polymers may be used in the present invention. Thus, the present photoimageable compositions may include one or more polymeric binders. Such mixtures of binder polymers can be two or more different branched binder polymers or one or more branched binder polymer combined with one or more unbranched binder polymers. The binder polymers may be mixed or blended in any suitable ratio. The particular ratio depends upon the specific binder polymers employed, whether they are branched or unbranched, and the specific properties desired. Such ratios are within the ability of one skilled in the art.

[0044] It is further preferred that the difunctional branched polymeric binders contain sufficient acid functionality to render the binder polymers soluble and removable upon development. The term "acid functionality" refers to any functionally capable of forming a salt upon contact with alkaline developer, such as dilute alkaline aqueous sodium or potassium hydroxide, e.g., 1 to 3 wt% solutions. Suitable acid functionality includes, but is not limited to, carboxylic acids, sulfonic acids, phosphonic acids and phenols. In general, the binder polymers have an acid number of up to about 250, preferably up to about 200. Typical ranges of acid numbers are from 15 to 250 and preferably from 50 to 250. Such acid numbers are based on the amount of KOH (potassium hydroxide) in mg to neutralize 1 g (dry weight) of binder polymer.

[0045] Suitable polymeric binders are generally commercially available from a variety of sources, such as Rohm and Haas Company (Philadelphia, Pennsylvania) or may be prepared by a variety of methods known in the literature. Typically, the polymeric binder is present in the photoimageable compositions in an amount of up to 90 wt%, based on the total weight of the composition, preferably from 20 to 80 wt%, more preferably from 25 to 85 wt%, and even more preferably from 30 to 80 wt%.

[0046] Monomers useful in the present photoimageable compositions are any which will polymerize into a network

around the branched polymeric binders. A wide variety of monomers may be used. Suitable monomers include, but are not limited to: methyl acrylate, 2-ethylhexyl acrylate, n-butyl acrylate, n-hexyl acrylate, methyl methacrylate, hydroxyethyl acrylate, butyl methacrylate, octyl acrylate, 2-ethoxyethyl methacrylate, t-butyl acrylate, 1,5-pentanediol diacrylate, N,N-diethylaminoethyl acrylate, ethylene glycol diacrylate, 1,3-propanediol diacrylate, decamethylene glycol diacrylate, decamethylene glycol dimethacrylate, 1,4-cyclohexanediol diacrylate, 2,2-dimethylol propane diacrylate, glycerol diacrylate, tripropylene glycol diacrylate, glycerol triacrylate, 2,2-di(p-hydroxyphenyl)-propane dimethacrylate, triethylene glycol diacrylate, polyoxyethyl-2,2-di(p-hydroxyphenyl)-propane dimethacrylate, triethylene glycol dimethacrylate, 1,3-propanediol dimethacrylate, butylene glycol dimethacrylate, 1,3-propanediol dimethacrylate, 1,2,4-butanetriol trimethacrylate, 2,2,4-trimethyl-1,3-pentanediol dimethacrylate, pentaerythritol trimethacrylate, 1-phenyl ethylene-1,2-dimethacrylate, pentaerythritol tetramethacrylate, trimethylol propane trimethacrylate, 1,5-pentanediol dimethacrylate, and 1,4-benzenediol dimethacrylate, styrene and substituted styrene, such as 2-methyl styrene and vinyl toluene and vinyl esters, such as vinyl acrylate and vinyl methacrylate.

[0047] The photoinageable compositions of the present invention contain one or more photoactive components. The photoactive components useful in the present invention are may be photoacid generators, photobase generators or free-radical generators. The present photoinageable compositions may be positive-acting or negative-acting, and preferably are negative-acting. It will be appreciated by those skilled in the art that mixtures of photoactive components allow the photoactivity of the compositions to be tailored to specific applications.

[0048] Suitable photoacid generators include halogenated triazines, onium salts, sulfonated esters, halogenated sulfonate decahydrides, diazodisulfones, α -cyanoxyaminesulfonates, imidesulfonates, ketodiazosulfones, sulfonylesters, 1,2-di(arylsulfonyl)hydrazines and the like. Particularly useful halogenated triazines include halomethyl-*o*-triazines.

[0049] Suitable free-radical generators include, but are not limited to, *n*-phenylglycine, aromatic ketones such as benzophenone, N,N'-tetramethyl-4, 4'-diaminobenzophenone [Michler's ketone], N,N'-tetraethyl-4, 4'-diaminobenzophenone, 4-methoxy-4'-dimethylaminobenzophenone, 3,3'-dimethyl-4-methoxybenzophenone, p,p'-bis(dimethylamino)benzophenone, p,p'-bis(diethylamino)benzophenone, anthraquinone, 2-ethylanthraquinone, naphthoquinone and phenanthraquinone, benzols such as benzoin, benzoinmethylether, benzoinisopropylether, benzoinn-butylether, benzoin-phenylether, methylbenzoin and ethylbenzoin, benzyl derivatives such as dibenzyl, benzyl-phenyldisulfide and benzylchloromethyl, acridone derivatives such as 8-phenylacridone and 1,7-bis(9-acridyl)heptane, thioxanthones such as 2-chlorothioxanthone, 2-methylthioxanthone, 2,4-diethylthioxanthone, 2,4-dimethylthioxanthone and 2-isopropylthioxanthone, acetophenones such as 1,1-dichloroacetophenone, p-t-butylchloroacetophenone, 2,2-dihydroxyacetophenone, 2,2-dimethoxy-2-phenylacetophenone, and 2,2-dichloro-4-phenylacetophenone, 2,4,5-triarylimidazole dimers such as 2-(p-chlorophenyl)-4,5-diphenylimidazole dimer, 2-(p-chlorophenyl)-4,5-di(m-methoxyphenyl)imidazole dimer, 2-(p-fluorophenyl)-4,5-diphenylimidazole dimer, 2-(p-methoxyphenyl)-4,5-diphenylimidazole dimer, 2-(p-methoxyphenyl)-4,5-diphenylimidazole dimer, 2,4-di(p-methoxyphenyl)-5-phenylimidazole dimer, 2-(2,4-dimethoxyphenyl)-4,5-diphenylimidazole dimer and 2-(p-methylmercaptophenyl)-4,5-diphenylimidazole dimer, and the like. Though, not a free-radical generator, triphenylphosphine may be included in the photoactive chemical system as a catalyst. Such free-radical generators are particularly suitable for use with negative-acting photoinageable compositions, and particularly suitable for use with negative-acting dry film photoinageable compositions of the present invention.

[0050] Typically, such photoactive components are present in an amount of from 0.05 to 10 wt% based on the total weight of the composition, preferably from 0.1 to 5 wt%, and more preferably from 0.1 to 2 wt%.

[0051] The present photoinageable compositions may be solvent-borne or water-borne. Whether such compositions are solvent- or water-borne depends upon the choice of polymer binder, including the choice of monomers and difunctional branch-point monomers used to prepare the polymer binders. Such choices of monomers and difunctional branch-point monomers is well within the ability of one skilled in the art. Thus, the present photoinageable compositions may optionally contain water, a solvent or a water-solvent mixture. Suitable solvents include, but are not limited to: ketone solvents such as acetone, methyl ethyl ketone, cyclohexanone, methyl isobutyl ketone and 2-heptanone; polyhydric alcohols and derivatives thereof such as ethylene glycol, ethylene glycol monoacetate, diethylene glycol, diethylene glycol monoacetate, propylene glycol, propylene glycol monoacetate, dipropylene glycol and dipropylene glycol monoacetate as well as monomethyl, monomethyl, monobutyl and monophenyl ethers thereof; cyclic ether solvents such as dioxane; ester solvents such as methyl lactate, ethyl lactate, methyl acetate, ethyl acetate, butyl acetate, methyl pyruvate, ethyl pyruvate, methyl methoxypropionate and ethyl ethoxypropionate; and amide solvents such as N,N-dimethyl formamide, N,N-dimethyl acetamide, N-methyl-2-pyrrolidone, 3-ethoxyethyl propionate, 2-heptanone, γ -butyrolactone, and mixtures thereof.

[0052] Optional additives that may be used in the present photoinageable compositions include, but are not limited to: anti-oxidation agents, plasticizers, speed enhancers, fillers, dyes, film forming agents, hydrophobic trihalomethyl containing photoresist strip enhancers and the like. Suitable plasticizers include esters such as dibenzoate esters.

5 Suitable hydrophobic trihalomethyl containing photoresist strip enhancers include a wide variety of compounds containing a trihalomethyl group which hydrolyzes to carboxylate anions during stripping of the photoresist. Preferably, such hydrophobic trihalomethyl containing photoresist strip enhancer is alpha-trichloromethyl benzyl acetate. Such optional additives will be present in various concentrations in a photoresist composition. For example, fillers and dyes may be used in relatively large concentrations, e.g. in amounts of from about 5 to 30 percent by weight, based on the total weight of the composition's dry components.

10 [00553] The photoresist compositions of the present invention are typically prepared by combining the branched polymeric binder, monomer, photoactive component, optional solvent and optional additives in any order.

[00554] Processing of the photoincurable or photoresist compositions of the invention may be in any conventional manner, in a typical procedure, a photoresist layer, either formed from a liquid composition or transferred as a layer from a dry film, is applied to a substrate. When a liquid photoresist composition is used, it may be applied to a substrate by any known means, such as spinning, dipping, roller coating and the like.

15 [00555] The present photoresist compositions may be used on a variety of substrates used in the manufacture of electronic devices such as printed wiring boards and integrated circuits. Suitable substrates include copper surfaces of copper clad boards, printed wiring board inner layers and outer layers, wafers used in the manufacture of integrated circuits and the like.

20 [00561] Once the photoresist is applied to the substrate, it is imaged or exposed to actinic radiation through appropriate artwork. In the case of a negative-acting photoresist, exposure of actinic radiation polymerizes the cross-linking agent in exposed areas, resulting in a cross-linked structure that is resistant to developer. Next, the composition is developed such as by using dilute alkaline aqueous solution. Suitable developers include 1-3 wt% aqueous solutions of sodium hydroxide or potassium hydroxide. Organic based developers, such as tetraalkylammonium hydroxide based developers, may be used but are less preferred.

25 [0057] During such development, the acidic groups of the binder polymers form salts which render the binder polymers soluble and removable. An advantage provided by the present polymeric binders is that

[0058] Thus, the present invention provides a method for forming a relief image including the steps of: a) disposing on a printed wiring board substrate a photoresist composition including a branched binder, a monomer and a photoactive component, wherein the branched polymeric binder includes as polymerized units one or more difunctional branch-point monomers having two polymerizable end groups and a backbone including one or more base cleavable functionalities, provided that if the difunctional branch-point monomer is free of urethane linkages (functionalities, provided that if the difunctional branch-point monomer is free of urethane linkages and both polymerizable end groups are (meth)acrylate esters the difunctional branch-point monomer has a molecular weight of ≥ 450 ; b) imaging the photoresist; and c) developing the photoresist.

30 [0059] In the case of negative-acting photoresists applied to copper surfaces of copper clad boards, an etchant may be used after development to remove copper from those areas where the photoresist was removed, thereby forming a printed circuit. The remaining resist is then removed using a stripper.

35 [0060] The present invention further provides a method of manufacturing a printed wiring board including the steps of: a) disposing on a printed wiring board substrate a photoresist composition including a branched polymeric binder, a monomer and a photoactive component, wherein the branched polymeric binder includes as polymerized units one or more difunctional branch-point monomers having two polymerizable end groups and a backbone including one or more base cleavable functionalities, provided that if the difunctional branch-point monomer is free of urethane linkages and both polymerizable end groups are (meth)acrylate esters the difunctional branch-point monomer has a molecular weight of ≥ 450 ; b) imaging the photoresist; and c) developing the photoresist.

40 [0061] The present photoresist compositions show enhanced removal as compared to conventional photoresists. Thus, the present invention also provides a method of enhancing the removal of a photoresist composition from a substrate including the step of combining a branched polymeric binder, a monomer and a photoactive component, wherein the branched polymeric binder includes as polymerized units one or more difunctional branch-point monomers having two polymerizable end groups and a backbone including one or more base cleavable functionalities, provided that if the difunctional branch-point monomer is free of urethane linkages and both polymerizable end groups are (meth)acrylate esters the difunctional branch-point monomer has a molecular weight of ≥ 450 to form a photoresist composition; disposing the photoresist composition of a substrate; imaging the photoresist composition; and developing the imaged photoresist composition. In conventional photoresists, the photoresist is stripped by action of a base on the polymerized monomer network, which is typically cleaved by the base. In conventional photoresists, however, the polymeric binders are at best "salted" by the base, meaning that pendant acid groups are converted to their corresponding salts, thus improving the water solubility of the binder polymers. While not intending to be bound by theory, it is believed that the present branched polymeric binders are also cleaved by the base used to strip the photoresist, thereby removing the resist by chemical breakdown of the polymer binder as well as by dissolution of the polymer binder. 45 [0062] It has also been surprisingly found that the present difunctional branch-point monomers used to prepare the present branched binder polymers do not adversely affect other properties of the photoresist binder such as chemical resistance. Thus, the present photoresist compositions also show improved adhesion as compared to conventional

photoresist compositions. Further, the present photoresist compositions show improved, i.e. faster, stripping with substantially no loss of chemical resistance, as compared to conventional photoresist compositions. Typically, as adhesion of a dry film photoresist is improved, the photoresist composition is harder to strip. The present photoresist compositions surprisingly provide both increased adhesion and improved stripping. Additionally, photoresist compositions of the present invention show increased photoresist as compared to conventional photoresist compositions containing polymeric binders that are not branched.

[0063] The present photoresist compositions are particularly suitable for use when small features are desired, such as less than or equal to 3 mil lines and spaces. Typically, such small features are harder to plate and thus the substrates, such as printed wiring boards, are left in the plating bath longer resulting in overplate. Such overplate makes removal of conventional photoresists difficult. An advantage of the present invention is that the photoresist is easily and rapidly removed, even from underneath such overlaid metal, as compared to conventional photoresists.

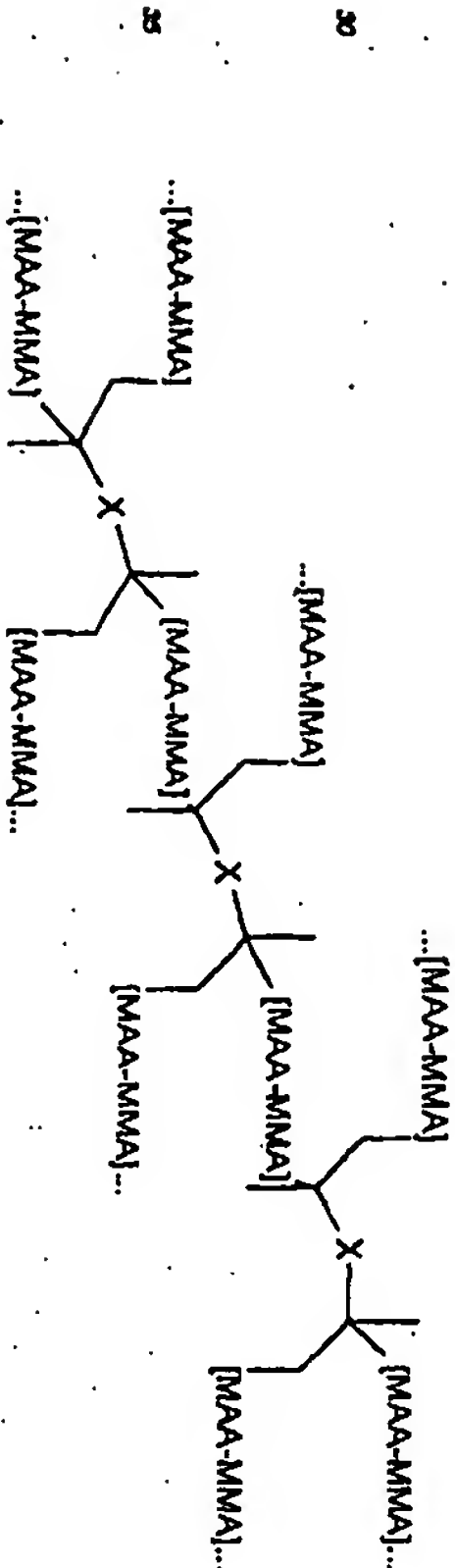
[0064] The following examples are intended to illustrate further various aspects of the present invention, but are not intended to limit the scope of the invention in any aspect.

Example 1

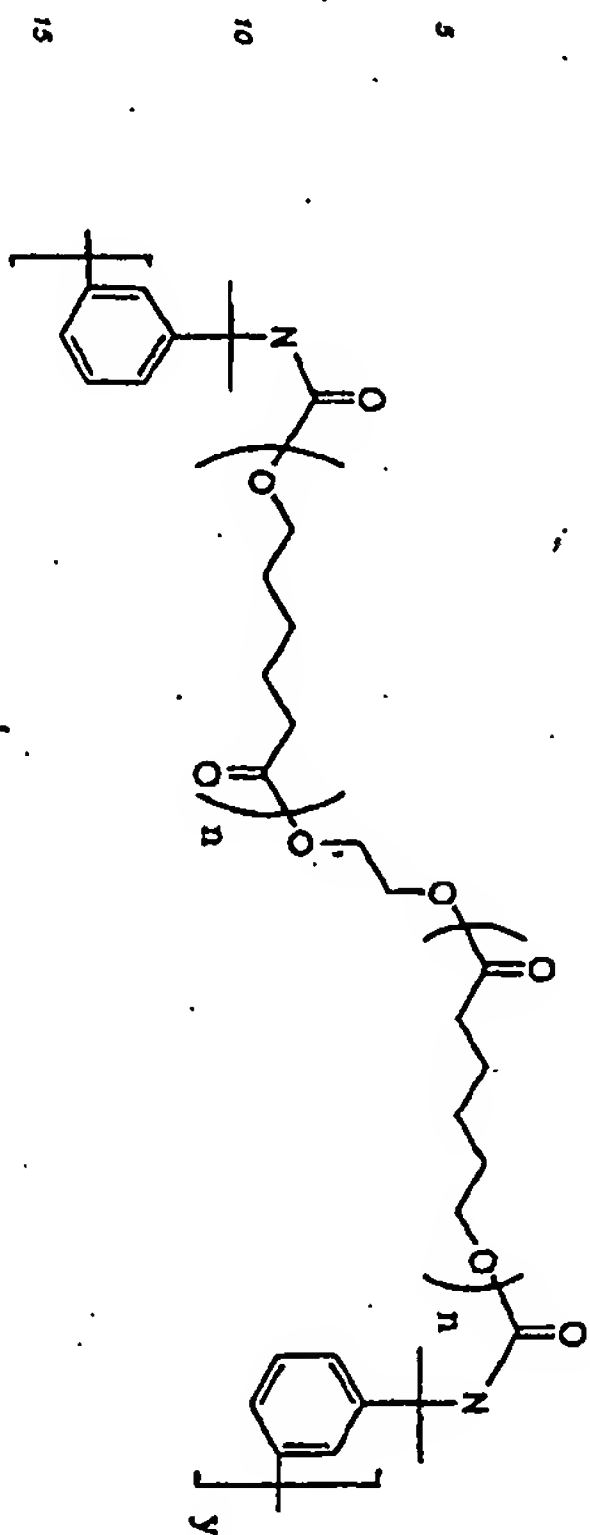
[0065] Two binder polymers were prepared as follows.

[0066] Comparative Binder: A monomer mixture (25% methacrylic acid, 75% methyl methacrylate) was diluted to 36% by weight with methyl ethyl ketone and then brought to reflux. An initiator was added to initiate the polymerisation reaction. Periodic additions of the initiator were added thereafter until the monomers were polymerized.

[0067] Branched Binder 1: A monomer mixture of 25% methacrylic acid, 71.5% methyl methacrylate, 3.5% of a moiety containing base cleavable functionalities having the formula pdrb-pcp0200-pdrb, where the "dashes" represent urethane linkages was diluted to 36% by weight with methyl ethyl ketone and then brought to reflux. An initiator was added to initiate the polymerization reaction. Periodic additions of initiator were added thereafter until the monomers were polymerized. The resulting branched binder had the generalized structure:



wherein X has the generalized structure:



and wherein $y = 1$ and $n = 2$. In the above structure, MMA refers to methyl methacrylate and MAA refers to methacrylic acid. The ellipses indicate that the MMA-MAA units are further attached to other MMA-MAA units as well as other branch-point monomers, forming a network having a finite, i.e. not infinite, molecular weight.

Example 2

[0068] Photoresist compositions were prepared by combining the polymer binders from Example 1 (53 wt%) with bisphenol A, 10 ethoxy dimethacrylate monomer (43 wt%), commercially available initiator 1 (3.5 wt%), commercially available initiator 2 (0.05 wt%), green background dye (0.05 wt%), antioxidant (0.2 wt%) and flow additive (0.2 wt%). The above ingredients were mixed to a 50% solids mixture in a 4:1 mixture of methyl ethyl ketone and iso-propanol. After mixing for 2 to 4 hours using a lab mixer, the 50% solids mixture was dried on 0.8 mil thick polyester at approximately 80° C for 3 to 8 minutes. The 50 micron thick, dried photoresist (less than 1.0% residual solvents) was then covered with 1.0 mil thick polyethylene forming a package of polyester / resist / polyethylene (finished "dry film").

Example 3

[0069] The negative working, photoresist composition from Example 2 was hot roll laminated to a cleaned, copper clad panel. The laminated panel were then covered with an artwork (photoresist) and imaged with UV radiation using an Opilbeam 7100 with enough energy to achieve a copper step 9 using a Stouffer 21 Step Wedge. After exposure, the polyester sheet was removed and the resist was then developing in 1% sodium carbonate monohydrate at 30° C. In the development process, the unexposed resist was removed. After development, the remaining (exposed) lines were examined for defects. The smallest lines with no defects and with 400 microns spaces were recorded as the fine line adhesion. Smaller lines are more easily attracted in the developing solution and by the conveyor equipment, thus a lower number indicates better adhesion. After examining the developed lines, the panels were then plated in a copper sulfate electrolytic plating bath until the resist height (50 microns) was exceeded by 20% (60 microns of plating). The exposed resist was then stripped from the panel with 3% sodium hydroxide at 50° C. The resulting times for the complete removal of the photoresist were recorded. The results are reported in Table 1.

Table 1

Sample	Photospeed for Copper Step 9	Time Line Adhesion	Strip Time
Comparative	77 mJ	33 μ m	28.2 sec
1	65 mJ	27 μ m	18.5 sec

[0070] It can be clearly seen from these data that photoresist compositions of the present invention have improved

adhesion, increased photospeed and reduced stripping time as compared to conventional photoresists.

Example 4

[0071] Other suitable branched binder polymers were prepared according to Example 1. These polymers are reported in Table 2 in terms of the monomers used to prepare the polymers.

Table 2

Branched Polymer	BM1 (%)	BM2 (%)	BM3 (%)	BM4 (%)	CM1 (%)	CM2 (%)	CM3 (%)	CM4 (%)	CM5 (%)
A	1	-	-	-	-	-	20	73	6
B	2	-	-	-	-	-	20	72	6
C	-	1	-	-	-	-	25	74	-
D	-	2	-	-	-	-	25	73	-
E	-	3	-	-	-	-	25	72	-
F	-	3.5	-	-	-	-	25	71.5	-
G	-	4	-	-	-	-	25	71	-
H	-	5	-	-	-	-	25	70	-
I	-	7	-	-	-	-	25	68	-
J	-	-	1	-	-	-	25	74	-
K	-	-	2	-	-	-	25	73	-
L	-	-	3	-	-	-	25	72	-
M	-	-	4	-	-	-	25	71	-
N	-	-	5	-	-	-	25	70	-
O	-	1	-	-	-	5	25	69	-
P	-	1	-	-	-	10	25	64	-
Q	-	1	-	-	-	15	25	59	-
R	-	3	-	-	-	5	25	67	-
S	-	3	-	-	-	10	25	62	-
T	-	3	-	-	-	15	25	57	-
U	-	5	-	-	-	5	25	65	-
V	-	-	-	1	10	-	25	64	-
W	-	-	-	4	10	-	25	61	-
X	-	-	-	1	-	10	25	64	-
Y	-	-	-	2	-	10	25	63	-

[0072] All amounts in Table 2 are reported in percent by weight of the total weight of monomers used to prepare the polymer. The branch-point monomers ("BM") used were: BM1 = methacrylic anhydride; BM2 = pdmbi-pcp0200-pdmbi; BM3 = pdmbi-pcp0230-pdmbi; and BM4 = ethc14-hdi-ppg1000-hdi-ethc14. The conventional monomers ("CM") used were: CM1 = ethoxylated hydroxyethyl methacrylate; CM2 = ethc14; CM3 = methacrylic acid; CM4 = methyl methacrylate; and CM5 = n-butyl acrylate.

Example 5 (Comparative)

[0073] The procedure of Example 1 was repeated using monomers containing one or more base cleavable groups,

Monomer	(Meth)acrylic Functionality	Molecular Weight	Percent Incorporation	Gelation
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10	Dipropylene glycol diacrylate	2	242	2.0	Yes
	"	"	"	4.0	"
	"	"	"	8.0	"
15	Tripropylene glycol diacrylate	2	300	2.0	"
	"	"	"	4.0	"
	"	"	"	8.0	"
20	Pentaerythritol tetraacrylate	4	352	2.0	"
	"	"	"	4.0	"
	"	"	"	8.0	"
25	Trimethylolpropane 3 choxy triacrylate	3	428	2.0	"
	"	"	"	4.0	"
	"	"	"	8.0	"

As can be seen from the above data, monomers having (meth)acrylate esters as the polymerizable groups and having a molecular weight of < 450 gelled during the polymerizations. Thus, such monomers are unsuitable for use as branch-point monomers in preparing the branched polymers of the present invention.

1. A photoreactive composition comprising a branched polymeric binder, a monomer and a photoactive component, wherein the branched polymeric binder comprises as polymerized units one or more difunctional branch-point monomers having two polymerizable end groups and a backbone comprising one or more base cleavable functionalites, provided that if the difunctional branch-point monomer is free of urethane linkages and both polymerizable end groups are (meth)acrylate esters the difunctional branch-point monomer has a molecular weight of ≥ 450 .

2. The composition of claim 1 wherein the photoactive component is selected from 8-phenylacridine, n-phenylglycine, benzophenone, N, N'-tetramethyl-4,4'-diaminobenzophenone, N,N'-tetrabutyl-4,4'-diaminobenzophenone, 4-methoxy-4'-dimethylazurobenzophenone, 3,3'-dimethyl-4-methoxybenzophenone, p,p'-bis(dimethylamino)benzophenone, p,p'-bis(dialkylamino)benzophenone, anthraquinone, 2-ethylanthraquinone, napthalanthraquinone, phenanthraquinone, benzoin, benzoinmethylether, benzoinethylether, benzoinisopropylether, benzoin-n-butylether, benzoin-phenylether, methylbenzoate, ethylbenzoate, dibenzyl, benzyldiphenyldisulfide, benzyltrimethylketene, 1,7-bis(β-acetidinyl)heptane, 2-chlorothioxanthone, 2-methylthioxanthone, 2,4-dimethylthioxanthone, 2-isopropylthioxanthone, 1,1'-dichloroacetophenone, p-t-butylidichloroacetophenone, 2,4-dimethylthioxanthone, 2-isopropylthioxanthone, 1,1'-dichloroacetophenone, p-t-butylidichloroacetophenone, 2,2-diethoxyacetophenone, 2,2-dimethoxy-2-phenylacetophenone, 2,2-dichloro-4-phenoxyacetophenone, 2-(o-chlorophenyl)-4,5-diphenylimidazole dimer, 2-(o-chlorophenyl)-4,5-dl(in-methoxyphenyl)imidazole dimer, 2-(o-fluorophenyl)-4,5-diphenylimidazole dimer, 2-(o-methoxyphenyl)-4,5-diphenylimidazole dimer, 2-(o-methoxyphenyl)-4,5-diphenylimidazole dimer, 2,4-dl(p-methoxyphenyl)-5-phenylimidazole dimer, 2-(2,4-dimethoxyphenyl)-

4,5-diphenylimidazole dimer, 2-(p-methylmercaptophenyl)-4,5-diphenylimidazole dimer and mixtures thereof.

3. The composition of any one of claims 1 to 2 wherein the polymeric binder comprises sufficient acid functionality to render said photoimageable composition developable in alkaline aqueous solution.
4. The composition of any one of claims 1 to 3 wherein the polymeric binder has an acid number of from about 50 to about 250.
5. The composition of any one of claims 1 to 4 wherein the one or more base cleavable functionalities are selected from anhydrides, esters, carbonates, or sulfonyl esters.
6. The composition of any one of claims 1 to 5 wherein the branched polymeric binder comprises from 0.1 to 25 wt% of one or more branch-point monomers, based upon the total weight of monomers in the polymeric binder.
7. The composition of any one of claims 1 to 6 wherein the difunctional branch-point monomers comprise 2 or more base cleavable groups.
8. The composition of any one of claims 1 to 7 wherein the monomer is selected from methyl acrylate, 2-ethylhexyl acrylate, n-butyl acrylate, n-hexyl acrylate, methyl methacrylate, hydroxyethyl acrylate, butyl methacrylate, octyl acrylate, 2-ethoxyethyl methacrylate, t-butyl acrylate, 1,5-pentanediol diacrylate, N,N-diethylaminoethyl acrylate, ethylene glycol diacrylate, 1,3-propanediol diacrylate, decanediethylene glycol diacrylate, decanediethylene glycol dimethacrylate, 1,4-cyclohexanediol diacrylate, 2,2-dimethylolpropane diacrylate, glycerol diacrylate, tripropylene glycol diacrylate, glycerol triacrylate, 2,2-di(p-hydroxyphenyl)propane diacrylate, triethylene glycol diacrylate, polyoxyethyl-2,2-di(p-hydroxyphenyl)propane dimethacrylate, triethylene glycol dimethacrylate, polyoxypropyltrimethylolpropane triacrylate, ethylene glycol dimethacrylate, butylene glycol dimethacrylate, 1,3-propanediol dimethacrylate, butylene glycol dimethacrylate, 1,3-propanediol dimethacrylate, 1,2,4-butanetriol trimethacrylate, 2,2,4-trimethyl-1,3-pentanediol dimethacrylate, pentaerythritol trimethacrylate, 1-phenyl ethylene-1,2-dimethacrylate, pentaerythritol tetramethacrylate, trimethylolpropane trimethacrylate, 1,5-pentanediol dimethacrylate, 1,4-benzenediol dimethacrylate, styrene, substituted styrene, vinyl toluene, vinyl esters and mixtures thereof.
9. A method of manufacturing a printed wiring board comprising the steps of: a) disposing on a printed wiring board substrate a photoresist composition of any one of claims 1 to 8.
10. A method for forming a relief image comprising the steps of: a) disposing on a printed wiring board substrate a photoresist composition of any one of claims 1 to 8.

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